

U.S. moving on laser standards

The inaugural meeting of the U.S. Technical Advisory Group (TAG) for ISO/TC 172/SC 9/WG—Electro-Optical Systems/ Lasers was held in Los Angeles on June 15 in response to the ISO initiative to prepare international standards for lasers and related equipment.

ISO's work in this area is in reaction to the European Economic Community's interest in establishing standards for products distributed within Europe as a part of the lowering of tariff trade barriers in 1992. The EEC's standards writing body, CEN, has begun to work on standards for lasers and equipment incorporating lasers as part of their preparations for 1992.

The ISO secretariat directly involved in this work is DIN, the German standards organization. Since DIN is also the secretariat for ISO/TC 172, it would prefer to see one set of international standards written, rather

than setting European standards first and writing international standards at a later date. This would not only mean less work, but would also allow for incorporating U.S. and Japanese input right from the start. For the U.S. to have any input, it must first have a position on this standardization work. Thus, the recent U.S. SC 9 meeting.

At the June meeting, Breck Hitz, executive director of the Laser and Electro-Optics Manufacturers Association (LEOMA, formerly the Laser Association of America), agreed to organize a second meeting in late summer in the Bay area for U.S. laser manufacturers. This session would be in preparation for U.S. participation in the first international meeting of SC 9 to be held in Germany late this fall.

In a related action, the Optical Society will be sponsoring the administrative work of the U.S. TAG for ISO/

TC 172/SC 9. While details of the interaction of the various organizations have not been settled, OSA and its members should benefit from increased communications in the standards arena, particularly regarding lasers and E/O equipment.

For further information about the SC 9 meetings, please contact Breck Hitz at LEOMA, 72 Mars St., San Francisco, Calif. 94114. The OSA contact for SC 9 is Evelyn Roberts, technical activities manager.

For many years, Walter J. Irving, representing the National Association of Photographic Manufacturers, Inc. (NAPM), was the administrator for the U.S. TAG for all of ISO/TC 172. Irving resigned from that post on July 1. His successor is Eduard R. Scherrer, NAPM, 550 Mamoroneck Ave., Harrison, N.Y. 10528.

—Robert E. Parks



NEW MEMBERS

New regular members

Andrauskas, Donna Marie
Cohn, Robert Warren
DeVilliers, Ann M.
Didier, Largeau
Grebel, Haim
Imani, Behzad
Jani, Mahendra G.
Marjoribanks, Robin S.
Maystre, Daniel Raymond
Nemoto, Shojiro
Neviere, Michel J.
Nunokawa, Kazuo
Senga, Yasuhiro

Shulman, Seth D.
Stratton, Suzanne Ruth
Swift, Dennis W.
Tong, F.
Weis, Antoine R.
van Brug, Hedser

New student members

Benefield, Clinton Daniel
Bever, Steven James
Blair, Loudon Thomas
Cairns, Brian
Cho, Nack Y.
De Vera, Albert J.N.
Gordon, Susanna P.
Gutierrez, Adolfo
LoPresti, Peter George
Maloney, John Michael
Marrin, Scott Michael
Metscher, Brian Douglas

Tin, Padetha
Vijaya, R.
Wismayer, Andrew Charles
Yamada, Masayuki

New corporate member

MTI Engineering Corp.